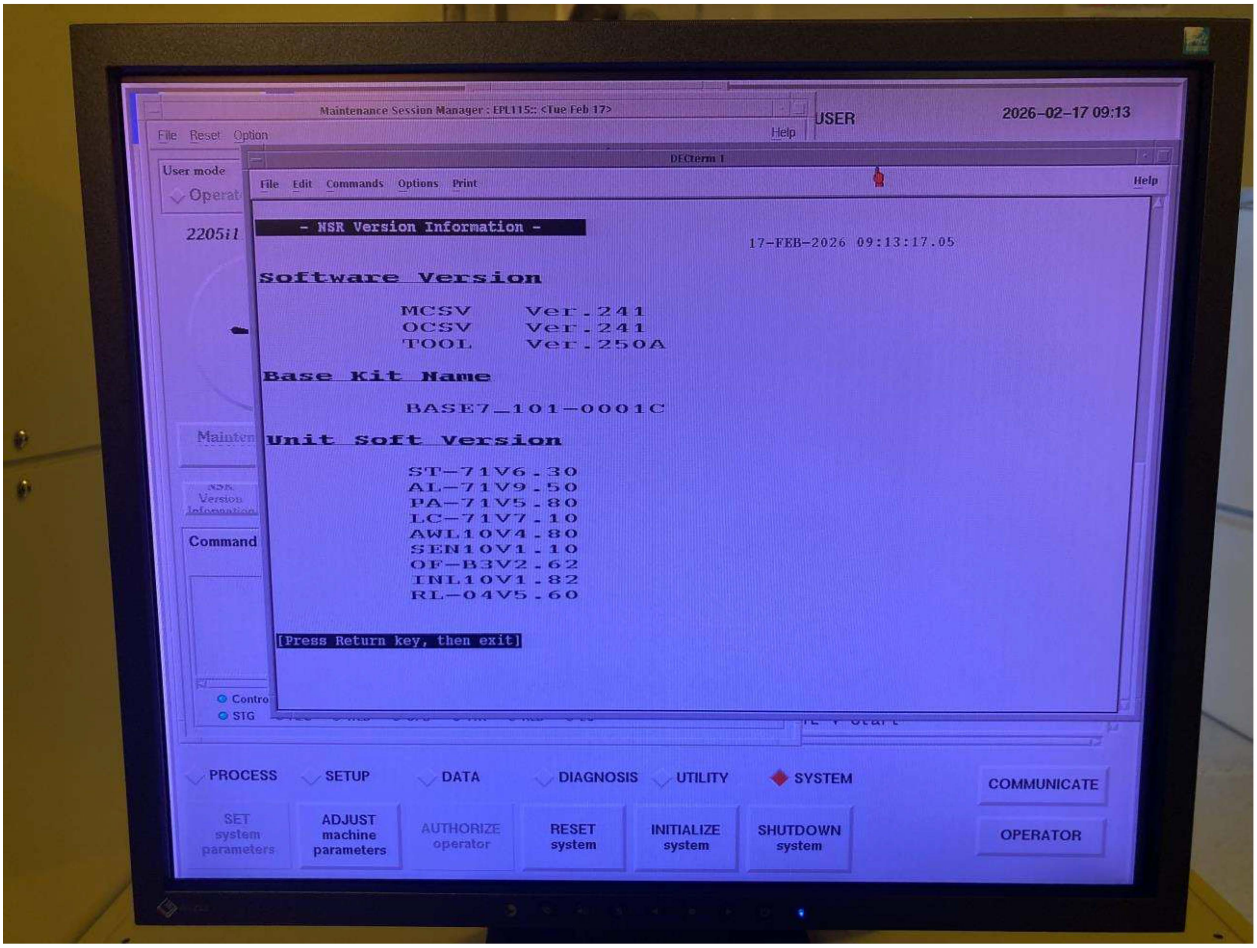
2205i11D

No	ITEM	SPEC	RESULT
1	Total Focus Deviation	Max-Min ≤ 0.20μm	0.290μm
2	Lens Astigmatism	|V-H| ≤ 0.30μm	0.233μm
3	Lens Dynamic Distortion	X,Y = Within ±50nm	Not Available
4	Wafer Flatness Accuracy	1) Flat Within ≥ Max-Min 3.0μm 2) L.F.S Within ≥ Max-Min 0.8μm	1. 0.89μm 2. 0.42μm
5	Exposure Power	Within ≥ 650mW/cm2	537mW/cm2
6	Illumination Uniformity	Within ±1.5%	1.01%
7	Stage Precision Accuracy 1) Stepping Accuracy 2) Backlash Accuracy	1) 3σ ≤ 50nm 2) 3σ ≤ 50nm	1) X: 14nm Y: 16nm 2) Not Available
8	Wafer Pre-Alignment Repeatability	3σ≦15μm	X : 4.580 μm Y : 21.51 μm T : 7.214 μm
9	Integrator Accuracy	Target: Ave ≤ 1%	Ave Max = 0.025%
10	Alignment Accuracy 1) FIA-EGA 2) LSA-EGA	FIA-EGA = |M| + 3σ ≤ 75nm LSA-EGA = |M| + 3σ ≤ 75nm	1) X = ±36nm Y = ±25nm 2) X= ±21nm Y = ±22nm

Software

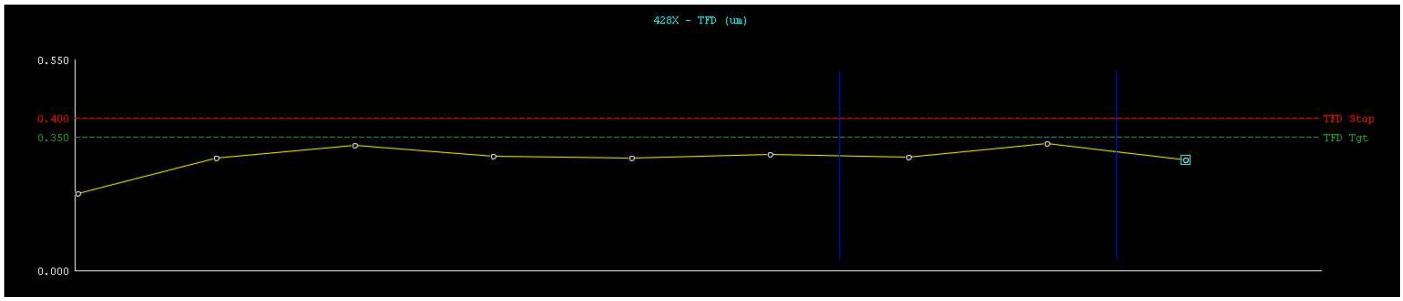

Maintenance Session Manager : EPL115:: <Tue Feb 17>
File Reset Option
Help
USER
2026-02-17 09:13
DECterm 1
File Edit Commands Options Print
Help
- NSR Version Information -
17-FEB-2026 09:13:17.05
Software Version
MCSV Ver.241
OCSV Ver.241
TOOL Ver.250A
Base Kit Name
BASE7_101-0001C
Unit Soft Version
ST-71V6.30
AL-71V9.50
PA-71V5.80
LC-71V7.10
AWL10V4.80
SEN10V1.10
OF-B3V2.62
INL10V1.82
RL-04V5.60
[Press Return key, then exit]
User mode
2205il
Command
PROCESS
SETUP
DATA
DIAGNOSIS
UTILITY
SYSTEM
COMMUNICATE
SET system parameters
ADJUST machine parameters
AUTHORIZE operator
RESET system
INITIALIZE system
SHUTDOWN system
OPERATOR

1. Total Focus Deviation:

(0.25µm L&S / 15Point V/H)

SPEC: Max-Min≤0.20µm

Result: Max – Min = 0.290µm

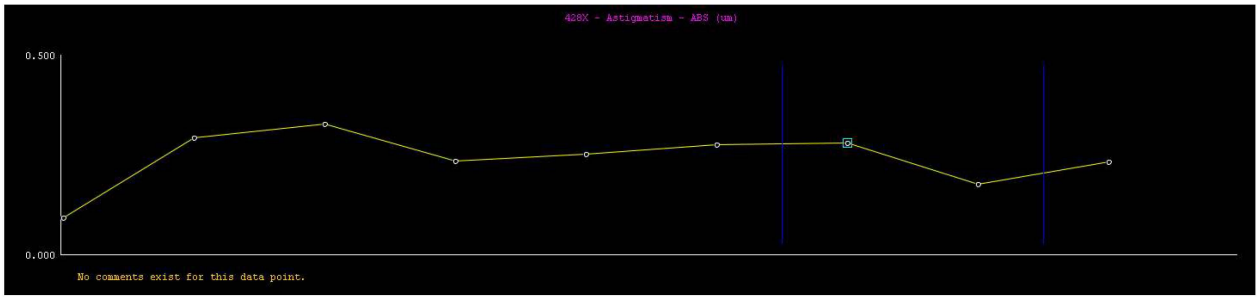


2. Lens Astigmatism :

(0.25µm L&S / 15Point V/H)

SPEC: |V-H| ≤0.20µm

Result: |V-H| = 0.233µm



3. Lens Dynamic Distortion :

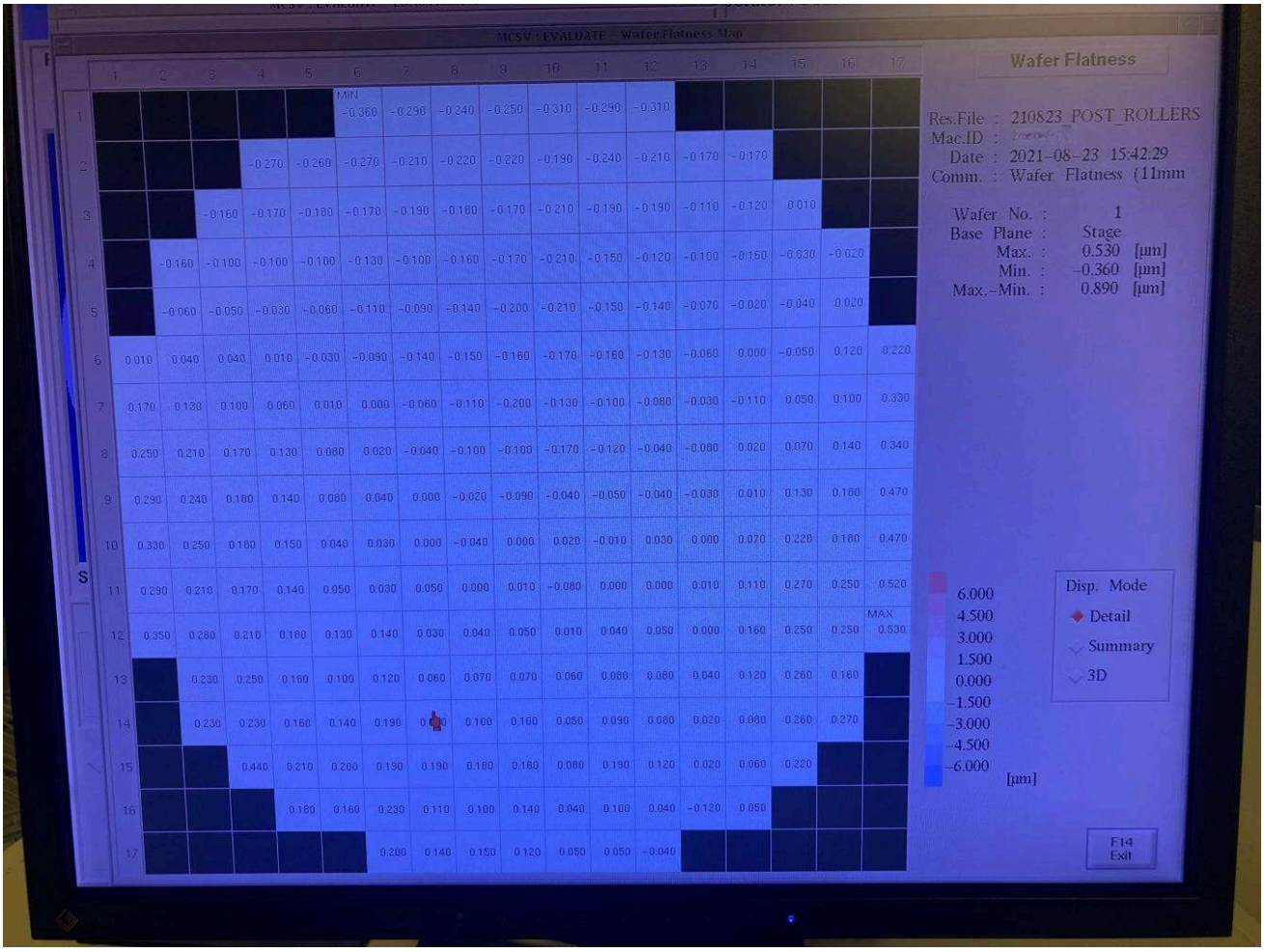
SPEC: X,Y = Within ±50nm

Result: Result not available, Measurement file purged

4. Wafer Flatness Accuracy :

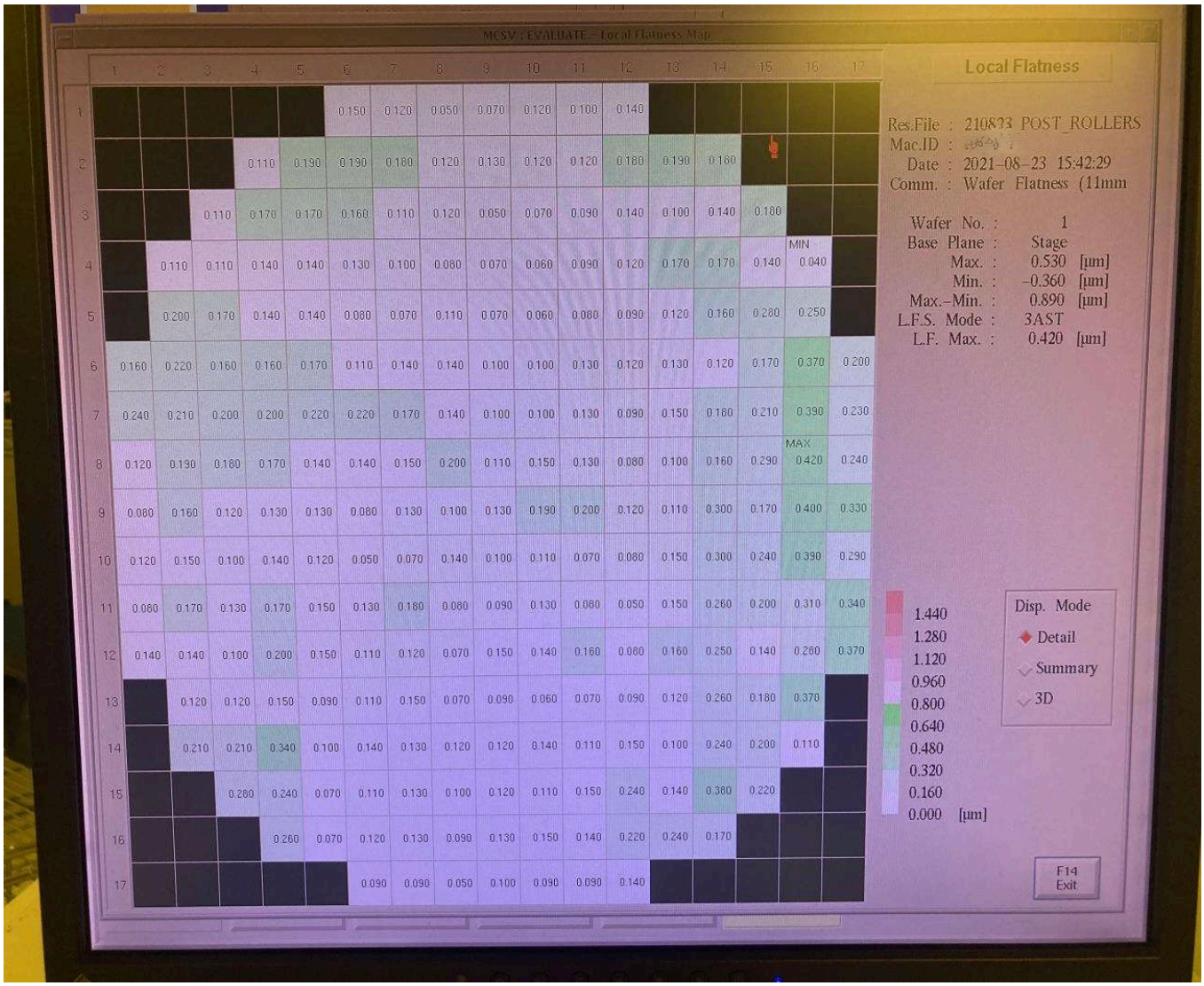
SPEC: 1) Flat Within ≥ Max-Min 3.0µm

Result: Max-Min = 0.89µm



SPEC: 2) L.F.S Within ≥ Max-Min 0.8µm

Result: Max-Min = 0.42µm



5/6 Exposure Power / Uniformity :

SPEC: Power = Within ≥ 650mW/cm2

Spec: Uniformity Within ±1.5%

Result: 1) Illumination Power = 537mW/cm2

2) Uniformity = 1.01%

7. Stage Precision Accuracy :

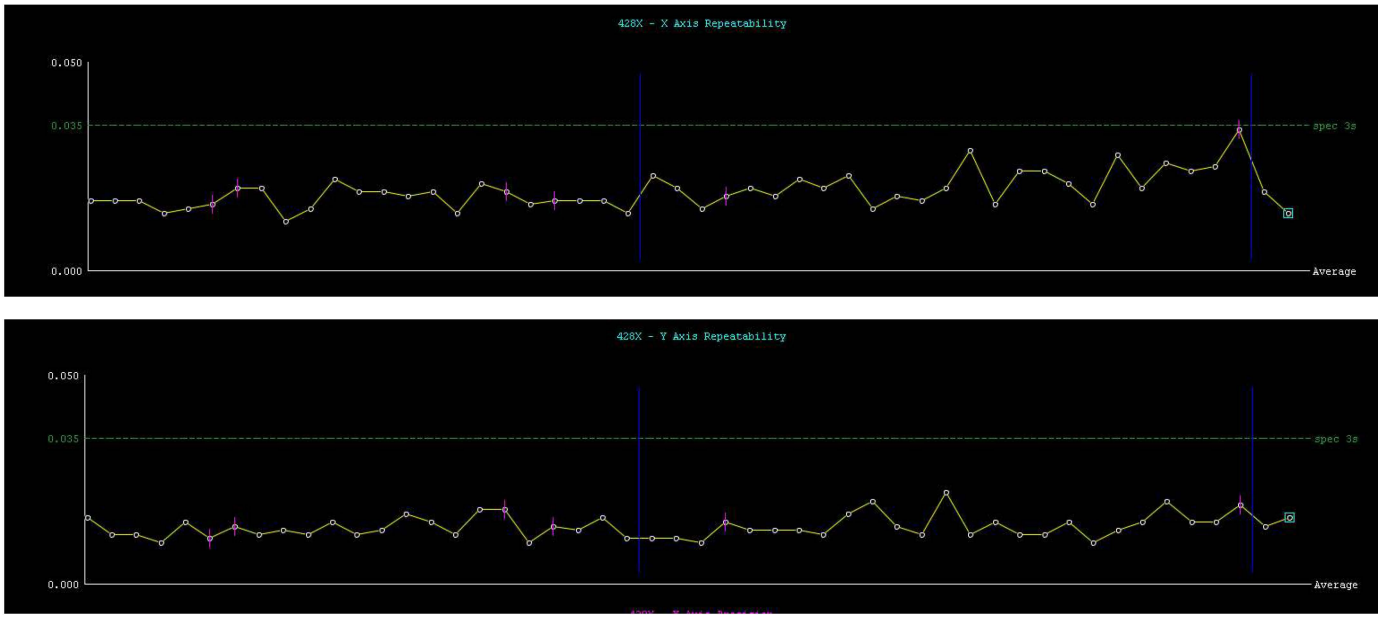
SPEC: Step X,Y 3σ ≤ 50nm

Backlash X,Y 3σ ≤ 50nm

Result:

1) Stepping Accuracy

X(3σ) : 14nm Y(3σ) : 16nm



2) Backlash Accuracy

Not available Measurement file purged

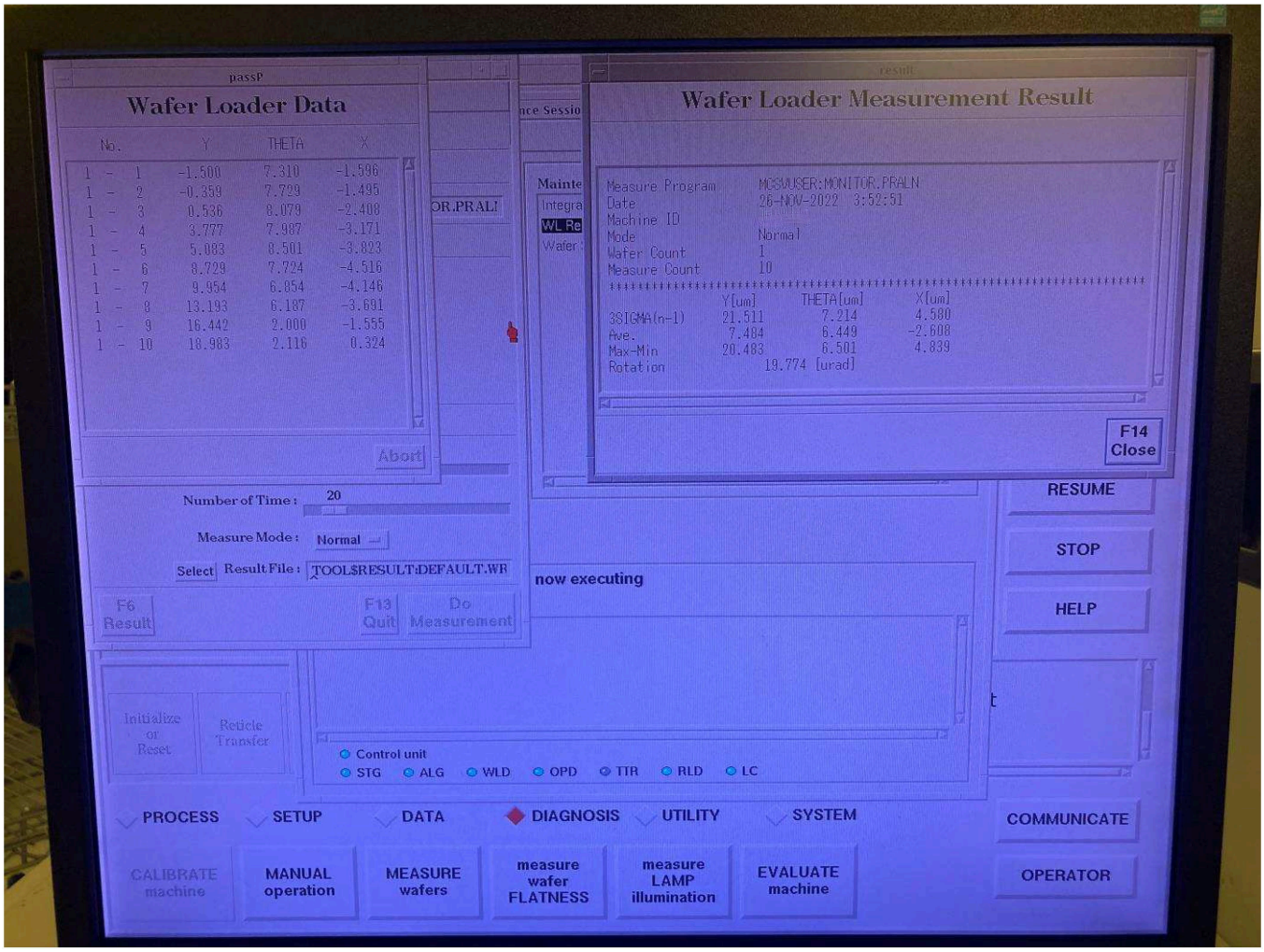
8. Wafer Pre-Alignment Repeatability :

SPEC: 3σ ≤ 15μm

Result: X(3σ) = 4.580μm

Y(3σ) = 21.51μm

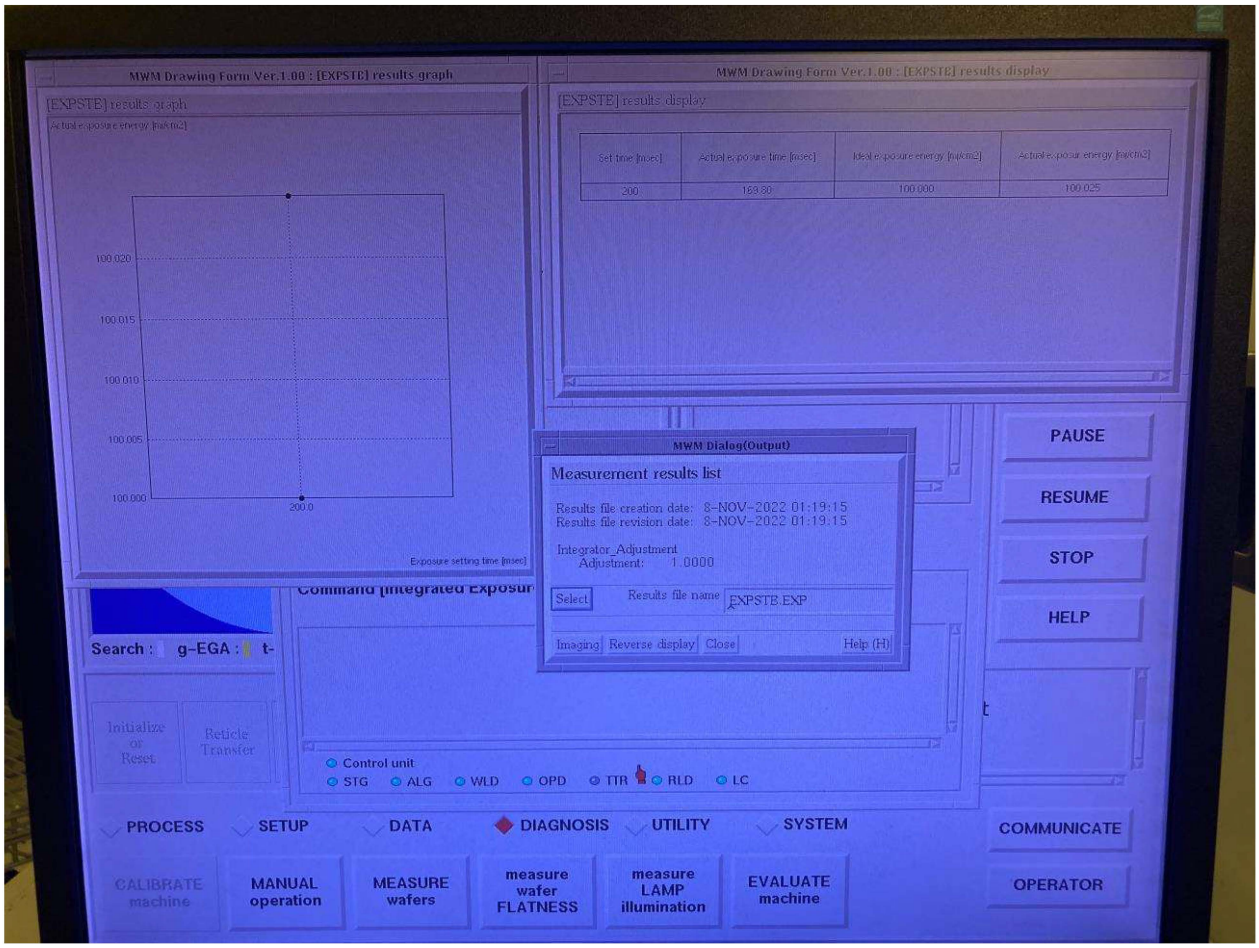
T(3σ) = 7.214μm



9. Integrator Accuracy :

SPEC: Ave ≤ 1.0%

Result: Max = 0.025%

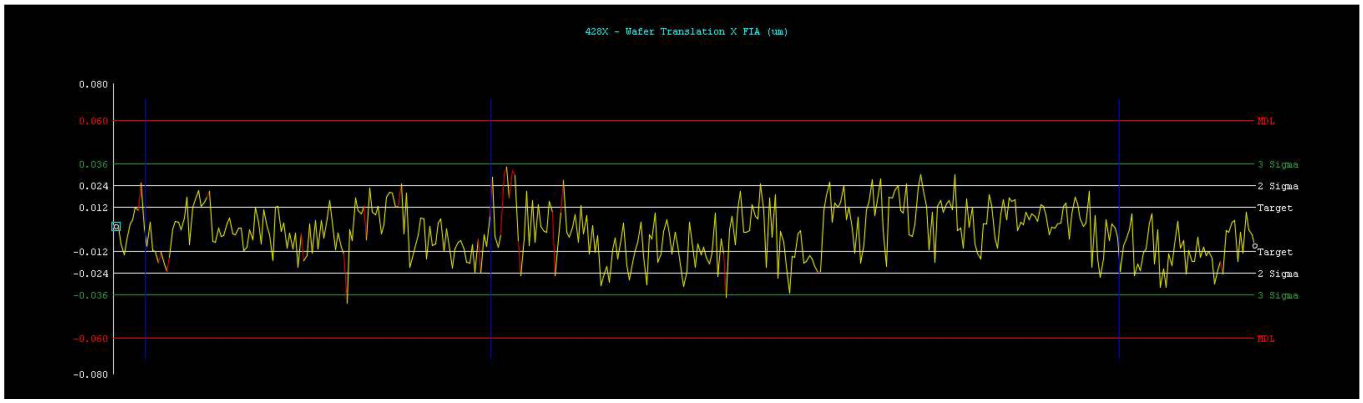


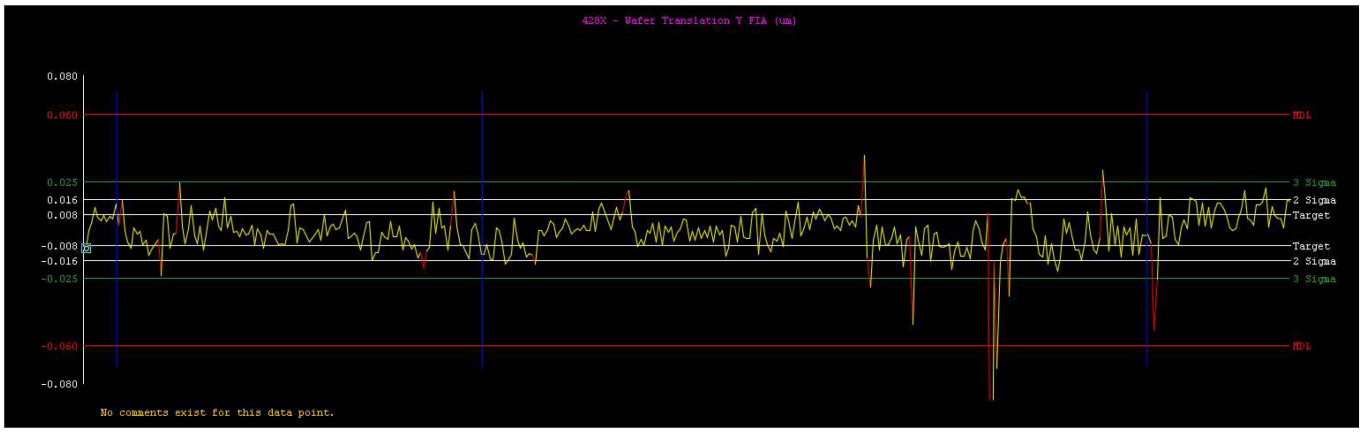
10-1 FIA :

SPEC: FIA-EGA = |M| + 3σ ≤ 70nm

Result: FIA-EGA X = 36nm

FIA-EGA Y = 25nm





10-2 LSA :

SPEC: LSA-EGA = |M| + 3σ ≤ 70nm

Result: LSA-EGA X = 21nm

LSA-EGA Y = 22nm